
Cross-sectional scanning tunneling microscopy of InAs/GaInSb and InAsP/InAsSb superlattices for infrared applications

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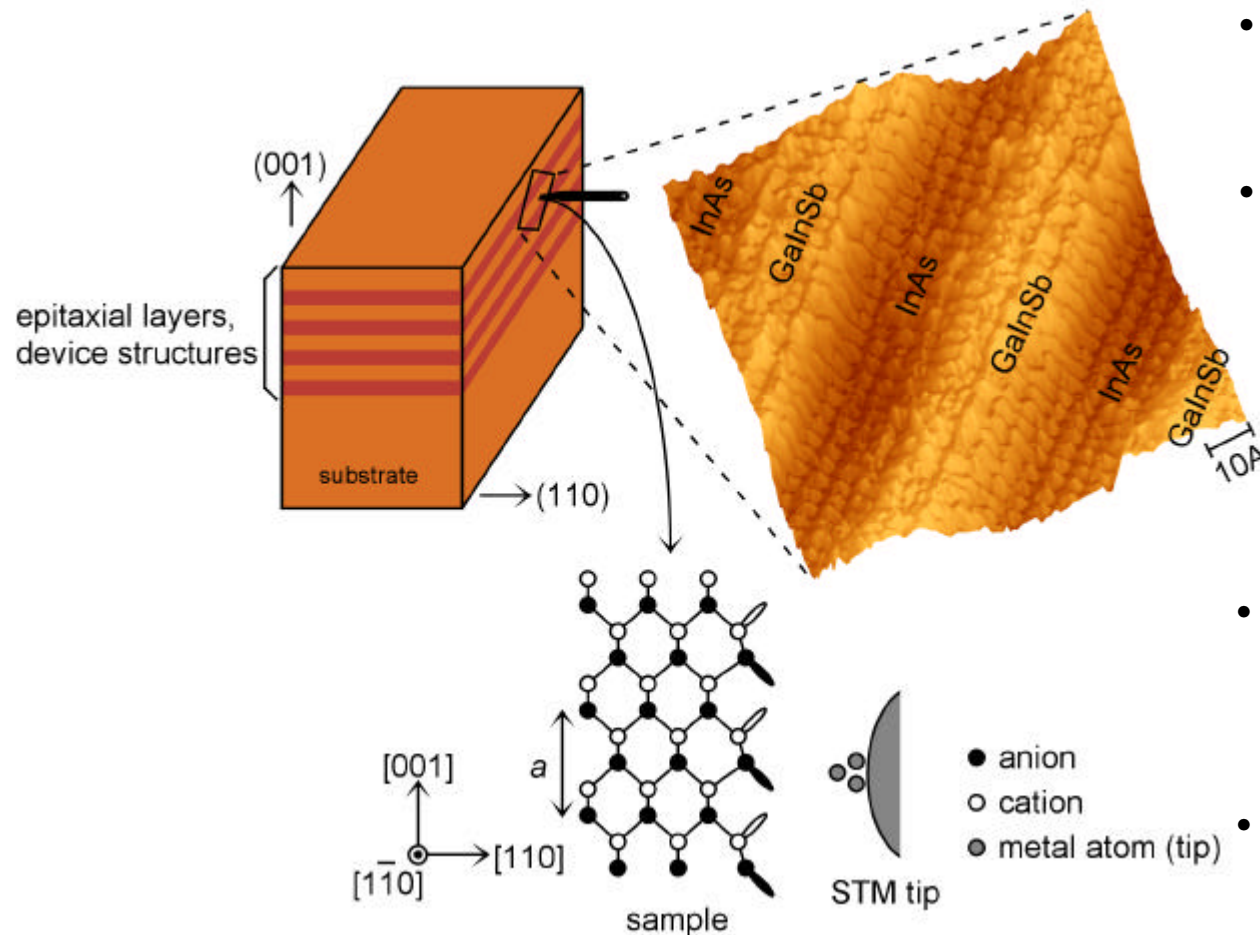
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Outline

- **Cross-sectional scanning tunneling microscopy**
- **Quantitative analysis of interface roughness in InAs/GaInSb superlattices**
- **Correlation of interface roughness and carrier mobility**
- **Compositional structure in InAsP/InAsSb superlattices**
- **Summary**

Cross-Sectional Scanning Tunneling Microscopy

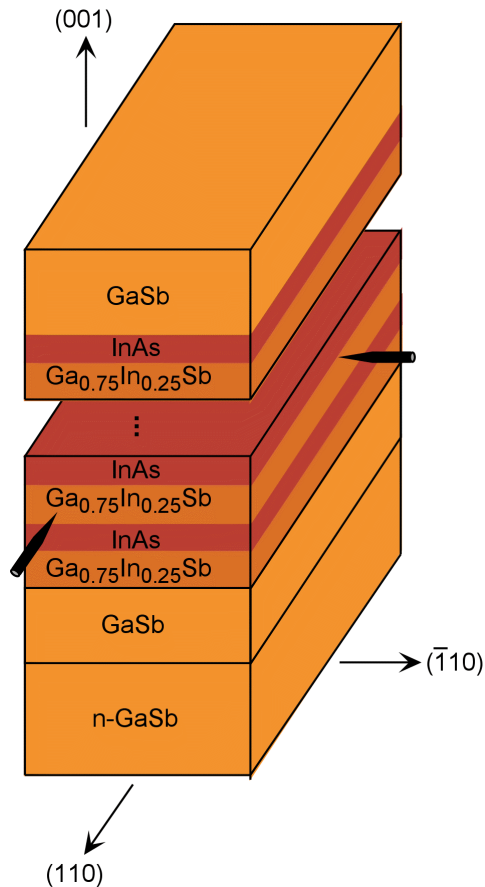


- Wafers are cleaved under ultrahigh-vacuum to expose {110} surfaces
- Tunneling measurements are performed on exposed cross-sections of epitaxial layers or devices
- {110} surfaces of III-V semiconductors generally remain 1x1; atomically flat {110} surfaces are generally unpinned
- Structure, electronic properties of epitaxial or device layers can be probed with atomic to nanometer-scale resolution

Interface Roughness in InAs/GaInSb Superlattices

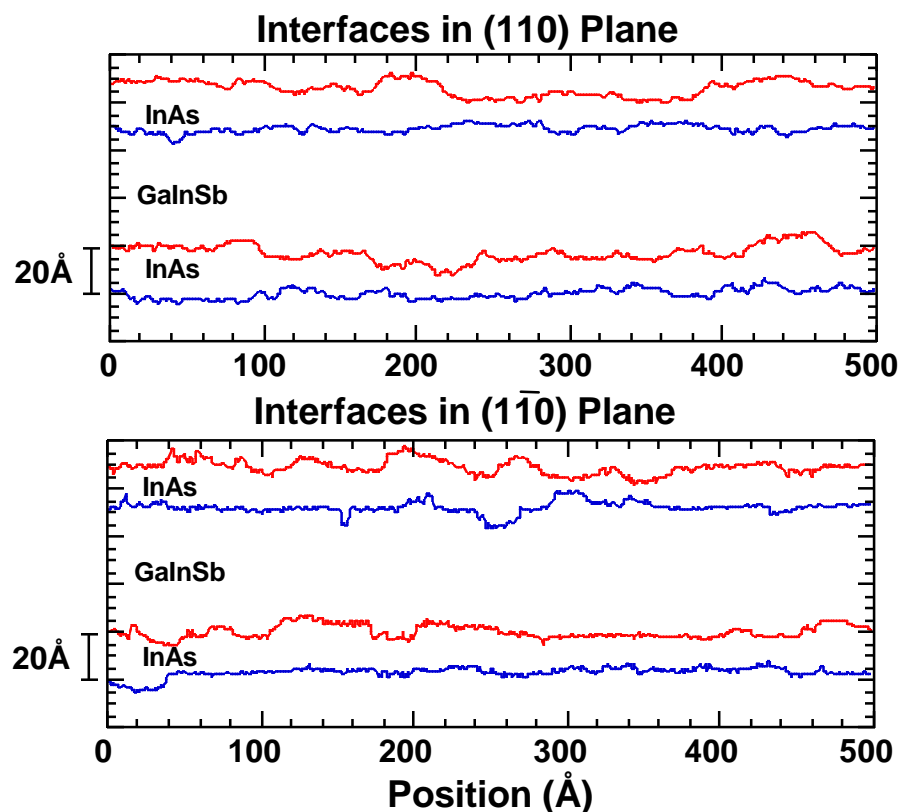
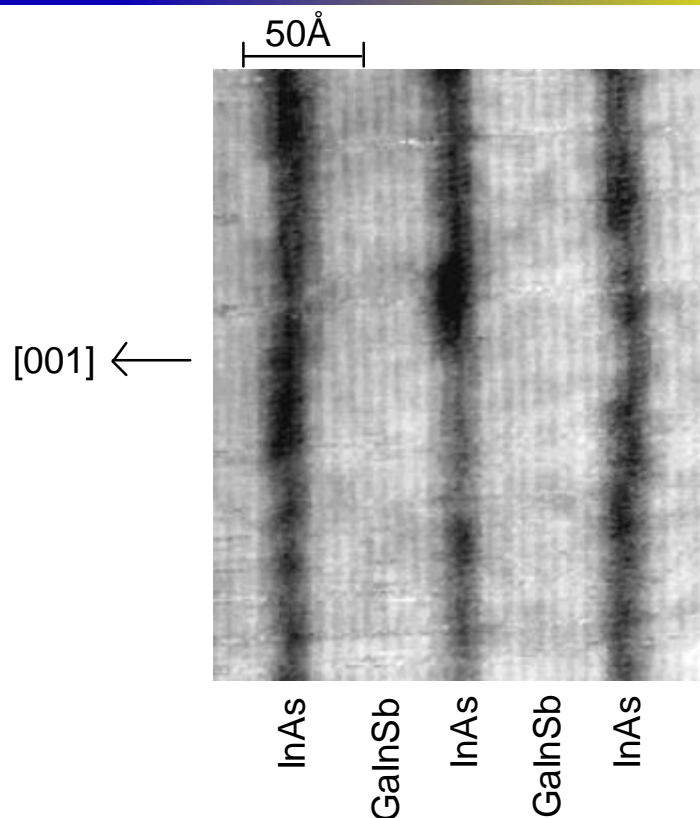
- Prior work in our group demonstrated qualitative asymmetry in As/Sb interface structure:
[A. Y. Lew et al., Appl. Phys. Lett. **65**, 201 (1994); J. Vac. Sci. Technol. B **14**, 2940 (1996).]
- Cross-sectional STM enables quantitative analysis of atomic-scale interface roughness:
[R. M. Feenstra et al., Phys. Rev. Lett. **72**, 2749 (1994).]
[S. L. Skala et al., J. Vac. Sci. Technol. B **13**, 660 (1995).]
[A. Y. Lew et al., Appl. Phys. Lett. **70**, 75 (1997); Phys. Rev. B **57**, 6534 (1998).]
- Detailed, quantitative analysis necessary to establish correlation between atomic-scale structure probed in STM studies and “macroscopic” properties, e.g., carrier transport, in actual device structures
- STM used to quantify atomic-scale interface roughness and dependence on:
Growth sequence: InAs-on-GaInSb vs. GaInSb-on-InAs
Orientation: (110) vs. ($\bar{1}\bar{1}0$)
- Quantitative measures of atomic-scale interface roughness obtained by STM compared to measurements of low-temperature carrier transport in InAs/GaInSb superlattice structures via simple modeling of interface roughness scattering

InAs/Ga_{1-x}In_xSb Sample Structure and STM Geometry



- Superlattice structure grown by MBE at HRL Laboratories:
 - n-GaSb (001) substrate, 1000Å GaSb buffer layer
 - 17Å InAs/52Å Ga_{0.75}In_{0.25}Sb, 150 periods
 - 500Å GaSb cap layer
 - T_g = 380°C
 - 5 s Sb soak at each interface
- Samples cleaved under UHV to expose either (110) or (1 $\bar{1}$ 0) cross-sectional planes
- STM characterization of both cross-sectional planes allows dependence of interface structure on orientation and growth sequence to be investigated

Quantitative Analysis of Interface Roughness

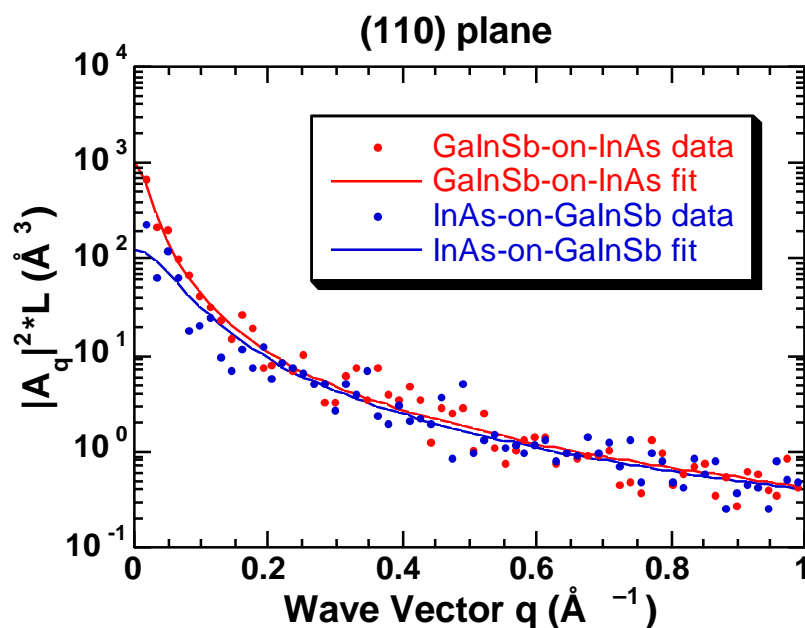


- STM imaging allows direct, quantitative investigation of atomic-scale interface structure:
(110) vs. (110)
GaInSb-on-InAs vs. InAs-on-GaInSb
- Fourier analysis yields spectral distribution of roughness amplitude:

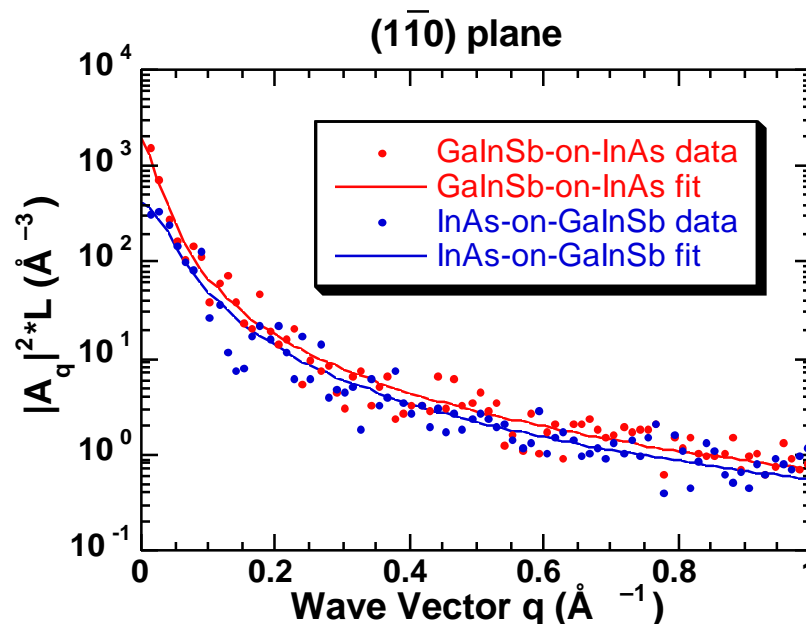
$$A_q = \frac{1}{N} \sum_{n=0}^{N-1} a(nd) e^{-iqnd}$$

$$|A_q|^2 = \frac{1}{L} \cdot \frac{2\Delta^2 (\Lambda/2p)}{1 + q^2 (\Lambda/2p)^2}$$

Spectral Distribution of Interface Roughness



GaInSb on InAs: $\Delta=3.2\pm0.2\text{\AA}$, $\Lambda=301\pm39\text{\AA}$
InAs on GaInSb: $\Delta=1.9\pm0.1\text{\AA}$, $\Lambda=112\pm16\text{\AA}$

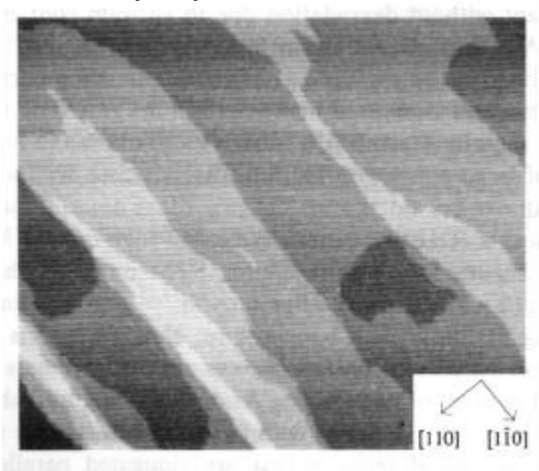


GaInSb on InAs: $\Delta=4.3\pm0.2\text{\AA}$, $\Lambda=327\pm38\text{\AA}$
InAs on GaInSb: $\Delta=2.8\pm0.2\text{\AA}$, $\Lambda=174\pm21\text{\AA}$

- Interfaces rougher in ($\bar{1}\bar{1}0$) plane compared to (110)
 - * Consistent with formation of islands elongated along $[\bar{1}\bar{1}0]$ during growth
- GaInSb-on-InAs interfaces rougher than InAs-on-GaInSb
 - * Consistent with laterally inhomogeneous composition at GaInSb-on-InAs interface

Orientation Dependence of Interface Roughness

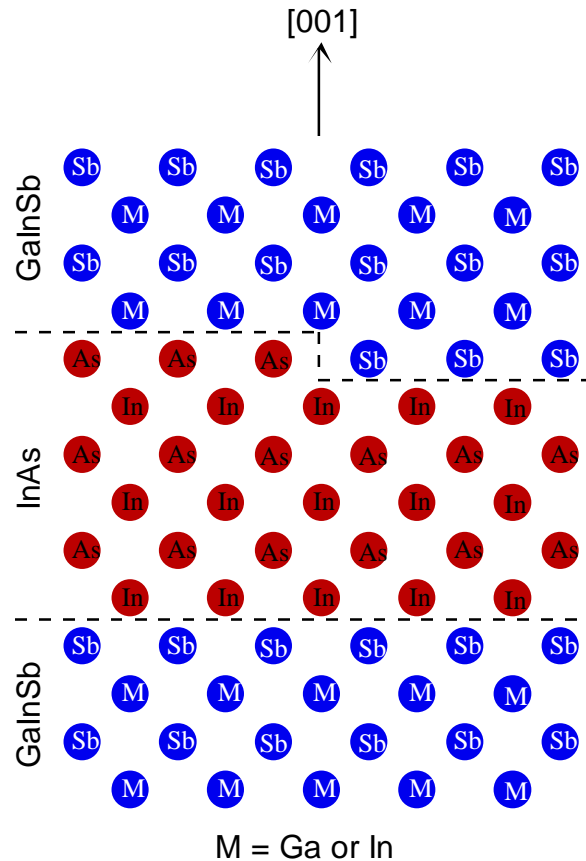
GaAs (001), 6000Åx6000Å:



[From E. J. Heller and M. G. Lagally, Appl. Phys. Lett. **60**, 2675 (1992).]

- In MBE growth of GaAs (001), islands and terraces form elongated along the $[1\bar{1}0]$ direction.
- Topographic features present during epitaxial growth are likely to produce roughness in heterojunction interfaces
- For islands and terraces running in the $[1\bar{1}0]$ direction, greater interface roughness would be expected in the $(1\bar{1}0)$ plane
- STM measurements demonstrate that interface roughness is greater in the $(1\bar{1}0)$ plane than in the (110) plane, consistent with surface topography observed in growth of GaAs (001).

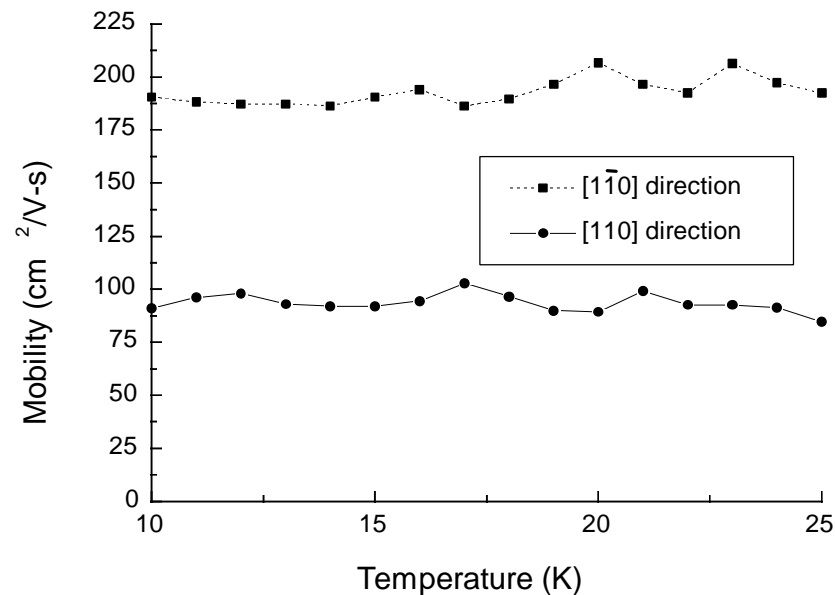
Dependence of Interface Roughness on Growth Sequence



- Prior studies have indicated that:
 - InAs-on-GaInSb interface is primarily InSb-like
 - GaInSb-on-InAs interface has mixed stoichiometry
- For growth of InAs on GaInSb, surface of GaInSb is already Sb-terminated
 - ⇒ InSb-like stoichiometry forms naturally
- For growth of GaInSb on InAs, formation of InSb-like interface requires that As termination of InAs be converted to Sb termination
 - ⇒ incomplete conversion produces mixed stoichiometry
- At interface with mixed stoichiometry, the position of the interface will vary with composition
 - ⇒ increased interface roughness
- Additional interface roughness will not be present at interfaces with uniform stoichiometry

Correlation of Atomic-Scale Structure with Transport Properties

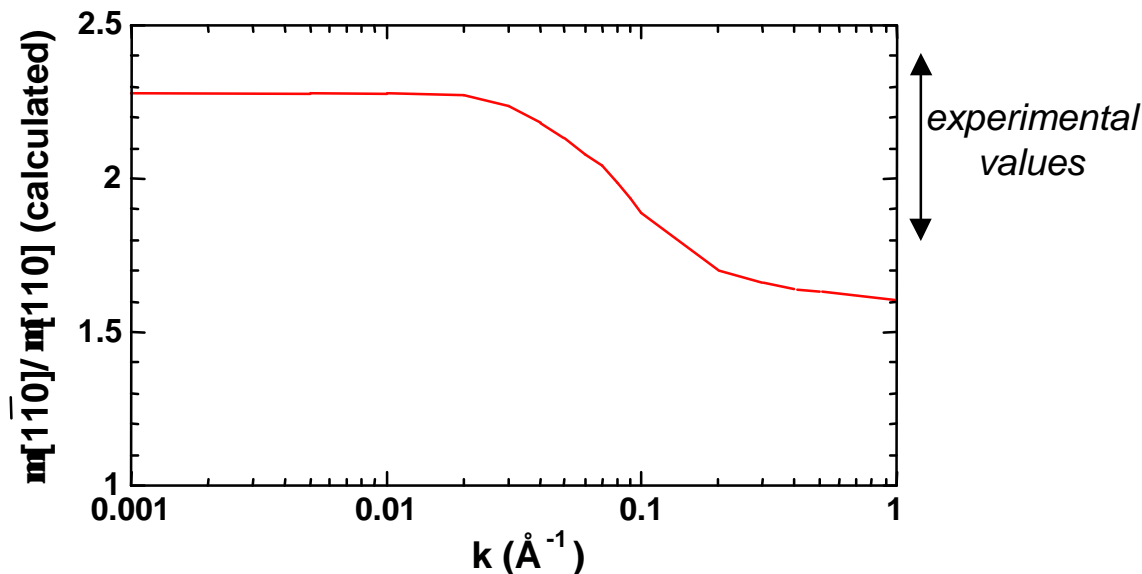
- Mobility in InAs/GaInSb superlattices has been found to be dominated at low temperatures by interface roughness scattering
- Modeling can be used to estimate quantitative effect of interface roughness anisotropy on carrier transport
- Transport measurements provide an opportunity to correlate atomic-scale morphology observed by STM with behavior of actual devices:



Transport Modeling and Results

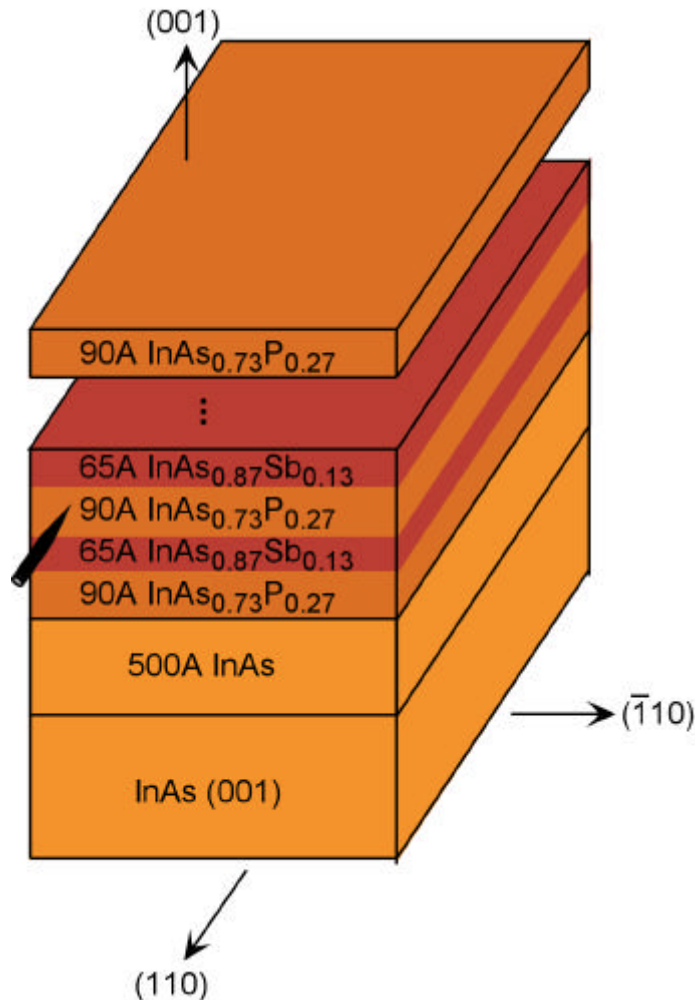
- Interface roughness data from STM used as input for estimate of scattering time:

$$\frac{1}{t(k)} = \frac{e^2 F_s^2 m^*}{2p\hbar^3} \int_0^{2p} dq (1 - \cos q) S(q) \left[\frac{\Gamma(q)}{e(q)} \right]^2, \quad q = 2k \sin q/2, \quad S(q) \sim \frac{p\Delta^2 \Lambda^2}{\left[1 + (q^2 \Lambda^2 / 2) \right]^{3/2}} \rightarrow m = \frac{e}{m^*} t$$



- Wave vectors $k \approx 0.01\text{-}0.1 \text{ \AA}^{-1}$ are most relevant for transport measurements
- Experimentally observed mobility anisotropy ratios for superlattices grown on GaSb (001) are $\sim 1.8\text{-}2.4$, in semiquantitative agreement with simple model
- Need to incorporate detailed superlattice band structure effects into modeling of transport

$\text{InAs}_{1-x}\text{P}_x/\text{InAs}_{1-y}\text{Sb}_y$ Heterostructures



- Sample grown by MOCVD at Sandia:
90Å $\text{InAs}_{0.73}\text{P}_{0.27}$ /65Å $\text{InAs}_{0.87}\text{Sb}_{0.13}$
10-period superlattice
InAs (001) substrate
- Similar superlattice structures used for fabrication of infrared LED's, lasers operating at 3.2-4.4μm
[S. R. Kurtz et al., *Appl. Phys. Lett.* **70**, 3188 (1997).]
[R. M. Biefeld et al., *J. Elec. Mater.* **26**, 1225 (1997).]
- Ordering, compositional clustering within superlattice alloy layers can influence band gaps, linewidths etc.

$\text{InAs}_{1-x}\text{P}_x/\text{InAs}_{1-y}\text{Sb}_y$ Heterostructures

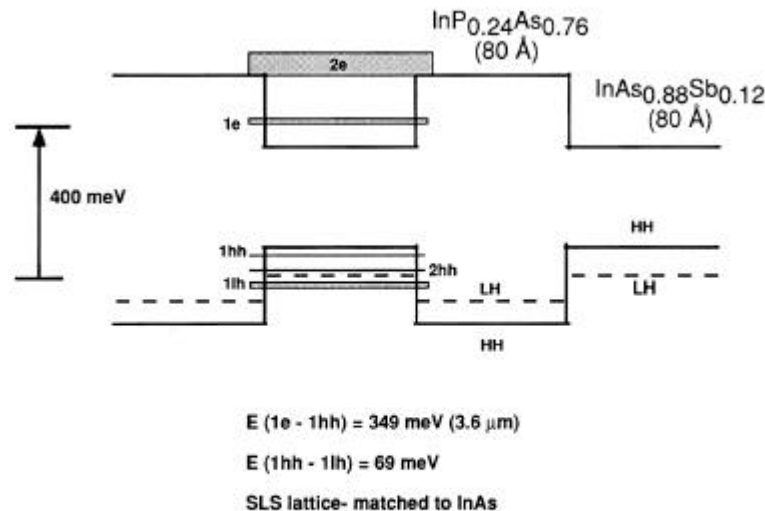
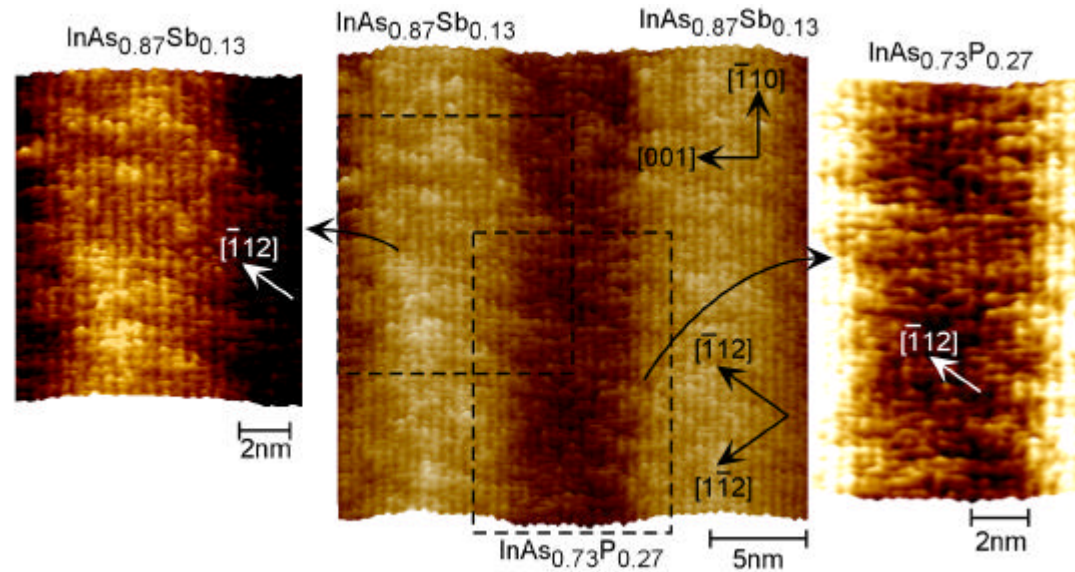


FIG. 1. Band alignments and quantum confinement state energies (drawn to scale) for an $\text{InAs}_{0.88}\text{Sb}_{0.12}/\text{InAs}_{0.76}\text{P}_{0.24}$ (80 Å/80 Å) SLS.

[From S. R. Kurtz et al., *Appl. Phys. Lett.* **70**, 3188 (1997).]

- Quantum-well optical properties will be highly dependent on structure of $\text{InAs}_{1-x}\text{P}_x$ and $\text{InAs}_{1-y}\text{Sb}_y$ alloy layers and of heterojunction interfaces
- Ordering could lead to reduction in bulk alloy energy band gaps
- Compositional clustering, interface roughness would lead to energy shifts, linewidth broadening
- Band alignment is such that:
 - $\text{InAs}_{1-y}\text{Sb}_y$ layer will appear higher in constant-current topographic image
 - As-rich regions in $\text{InAs}_{1-x}\text{P}_x$ and Sb-rich regions in $\text{InAs}_{1-y}\text{Sb}_y$ will appear higher in topographic image

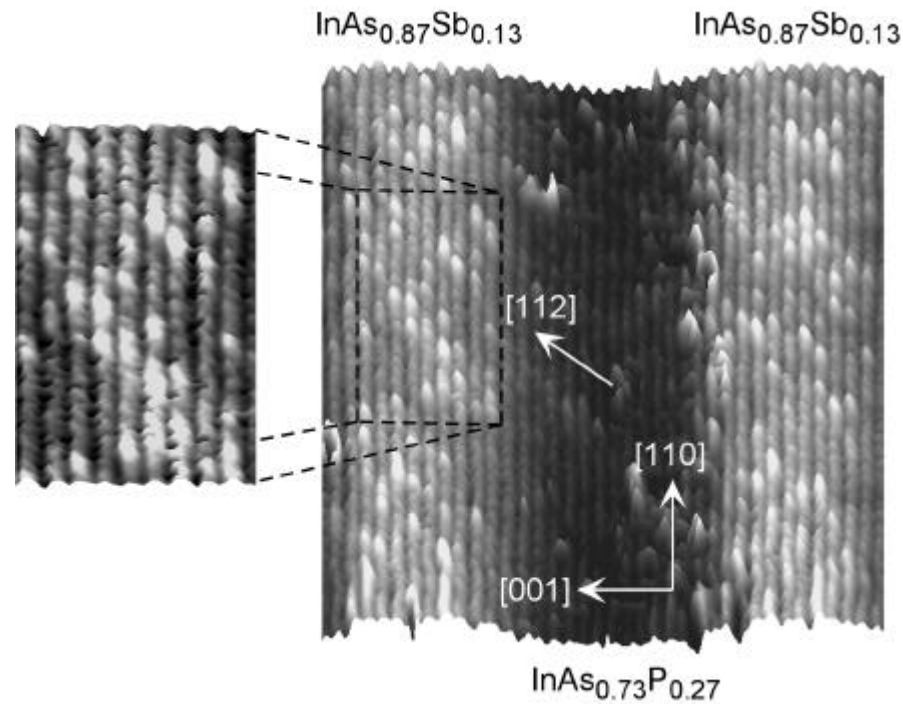
(110) Cross-Sectional Imaging of $\text{InAs}_{1-x}\text{P}_x/\text{InAs}_{1-y}\text{Sb}_y$ Structure



- Significant compositional inhomogeneity (clustering) observed in both $\text{InAs}_{1-x}\text{P}_x$ and $\text{InAs}_{1-y}\text{Sb}_y$
- P-rich regions (dark) in $\text{InAs}_{1-x}\text{P}_x$ layer appear preferentially aligned along $[\bar{1}12]$ direction
- Sb-rich clusters (bright) observed in $\text{InAs}_{1-y}\text{Sb}_y$ layer, no clear preferential orientation
- Cross-incorporation of Sb into $\text{InAs}_{1-x}\text{P}_x$ or P into $\text{InAs}_{1-y}\text{Sb}_y$ difficult to determine unambiguously
- Previously reported TEM studies showed partial ordering in $\text{InAs}_{1-y}\text{Sb}_y$ alloys with variations in relative strength of ordering along $[\bar{1}11]$, $[1\bar{1}1]$ directions

[D. M. Follstaedt et al., *J. Elec. Mater.* **24**, 819 (1995).]

$(\bar{1}10)$ Cross-Sectional Imaging of $\text{InAs}_{1-x}\text{P}_x/\text{InAs}_{1-y}\text{Sb}_y$ Structure



- Compositional fluctuations clearly visible in InAsSb layer
- Evidence of preferential orientation?

Summary

- **Cross-sectional STM provides atomic-scale information about heterojunction interface and alloy layer structure**
- **Quantitative analysis of InAs/GaInSb interface roughness reveals influence of stoichiometry, surface structure during growth on final interface structure**
- **Quantitative correlation established between interface roughness and carrier transport properties**
- **Preliminary studies of InAsP/InAsSb superlattices provide insight into nanoscale compositional structure of alloys**